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United States Patent [19]

Burkhart et al.

[11] **Patent Number: Des. 420,022**

[45] **Date of Patent: ** Feb. 1, 2000**

[54] **ELECTROSTATIC CHUCK WITH IMPROVED SPACING AND CHARGE MIGRATION REDUCTION MASK**

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[73] Assignee: **Applied Materials, Inc.**, Santa Clara, Calif.

[**] Term: **14 Years**

[21] Appl. No.: **29/081,238**

[22] Filed: **Dec. 24, 1997**

Related U.S. Application Data

[63] Continuation-in-part of application No. 08/639,841, May 8, 1996, Pat. No. 5,764,471.

[51] **LOC (7) Cl.** **15-09**

[52] **U.S. Cl.** **D15/140**

[58] **Field of Search** D15/140; 361/234, 361/235; 279/128; 269/8, 903

[56] **References Cited**

U.S. PATENT DOCUMENTS

5,528,451	6/1996	Su	279/128

Primary Examiner—Antoine Duval Davis
Attorney, Agent, or Firm—Thomason & Moser

[57] **CLAIM**

The ornamental design for an electrostatic chuck with improved spacing and charge migration reduction mask, as shown and described.

DESCRIPTION

FIG. **1** is a top view of the electrostatic chuck having the improved spacing and charge migration reduction mask;

FIG. **2** is an elevation view when looking to the right along the x-axis in FIG. **1**, the view when looking to the left along the x-axis in FIG. **1** being identical to that of FIG. **2** thereof;

FIG. **3** is a detailed view of part of the surface seen in FIG. **2** thereof;

FIG. **4** is a bottom view thereof;

FIG. **5** is an elevation view when looking down along the y-axis in FIG. **1** thereof; and,

FIG.**6** is an elevation view when looking up along the y-axis in FIG. **1** thereof.

1 Claim, 2 Drawing Sheets

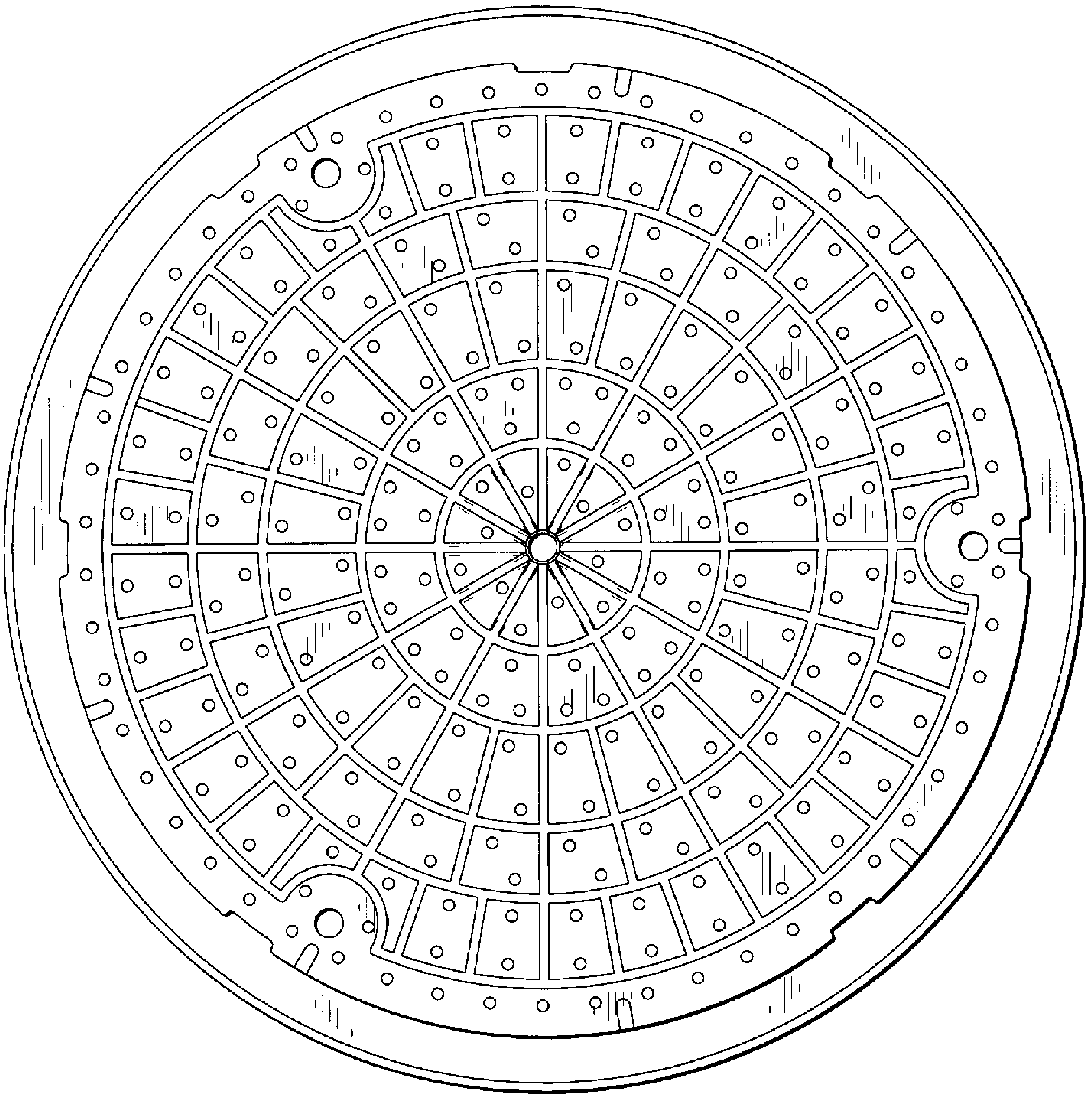

FIG. 1

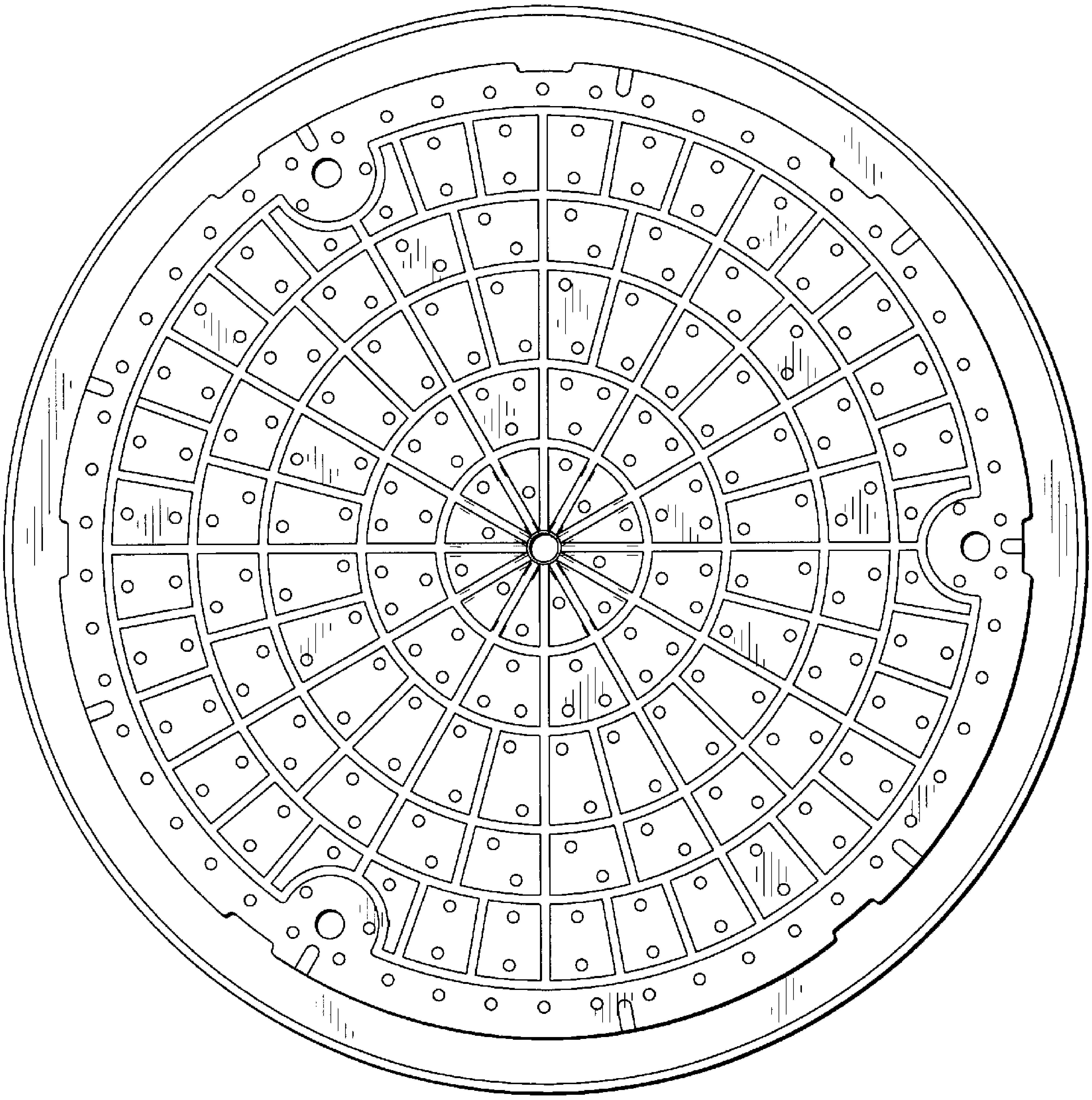

FIG. 2

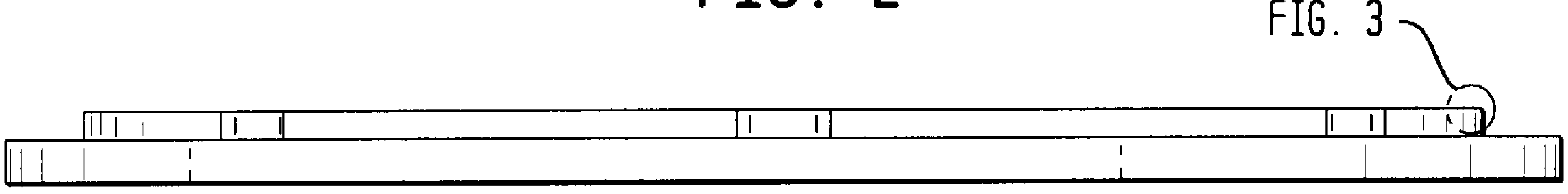

FIG. 3

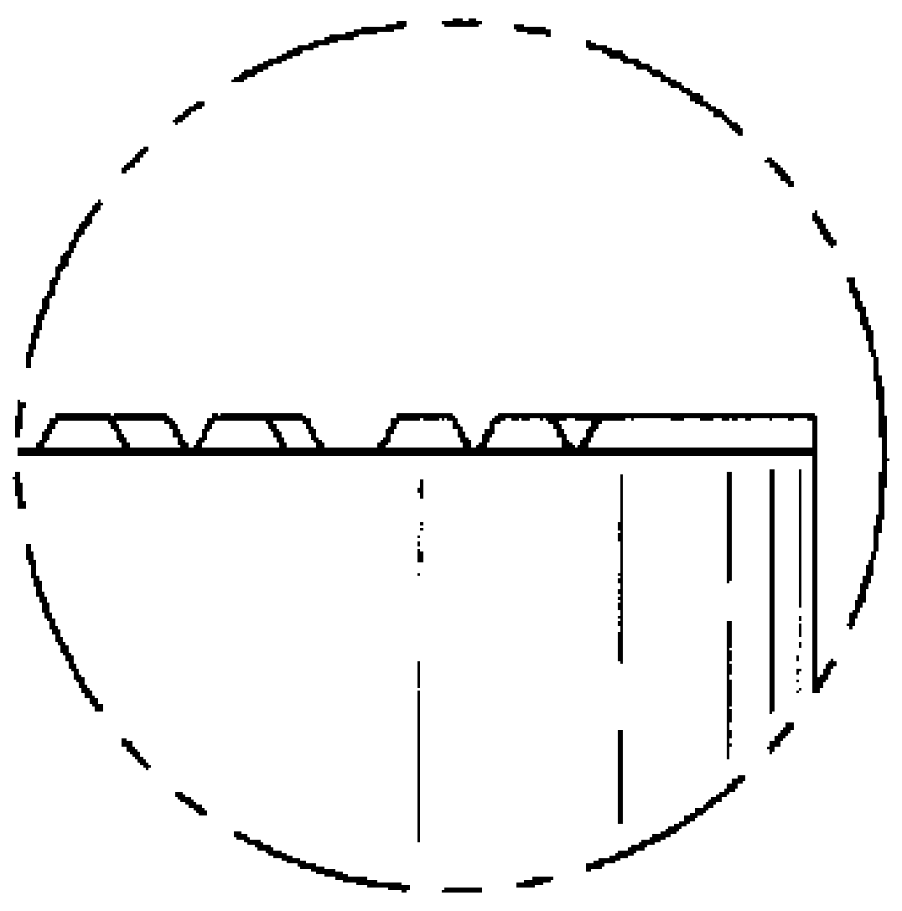

FIG. 4

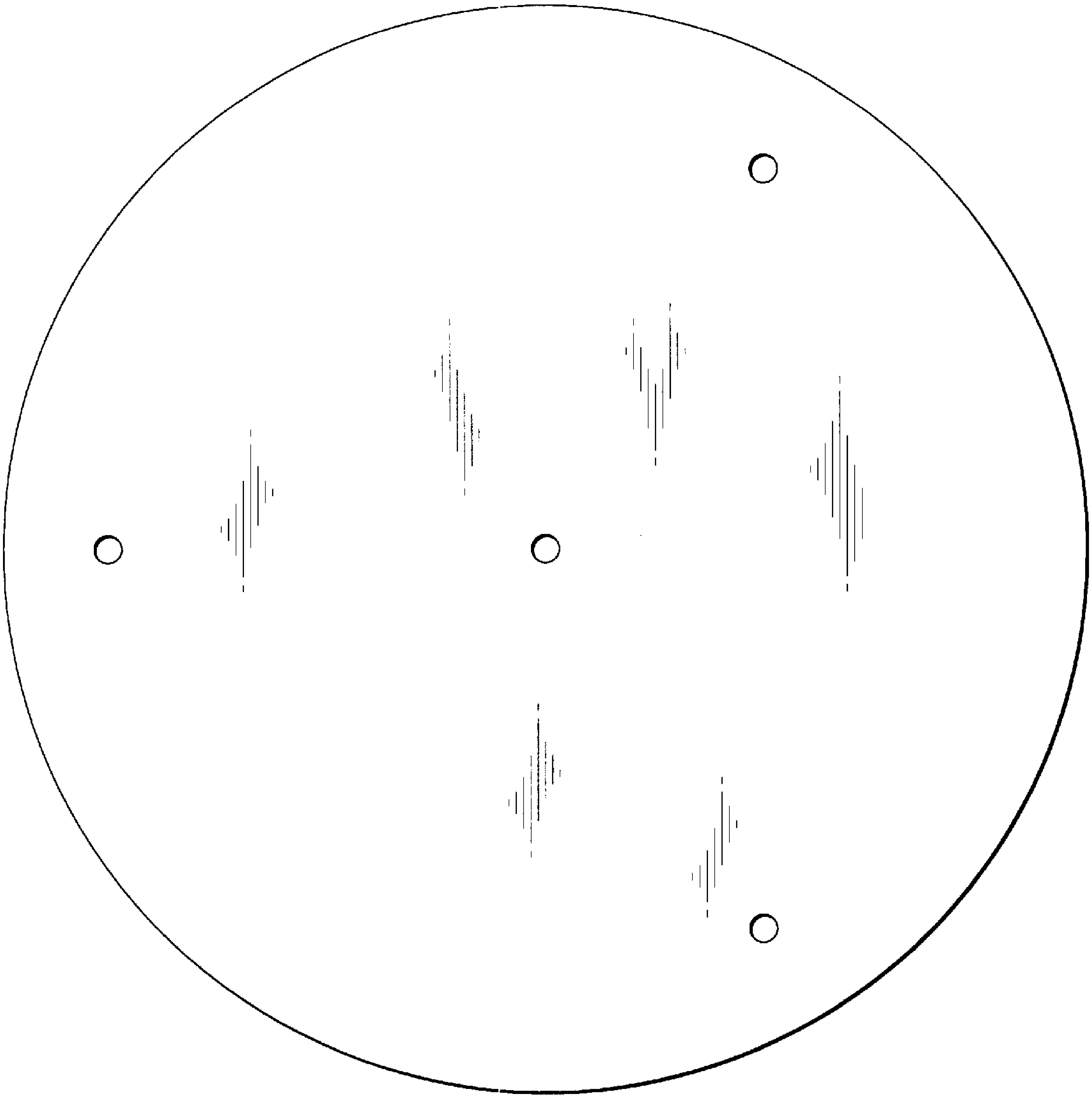

FIG. 5

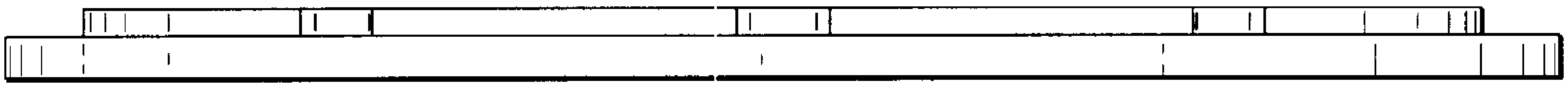

FIG. 6